

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L2	40639	(position\$3 or elevat\$3) adj3 ((substrate or wafer or workpiece or work or article) adj3 (holder or table or support or stage or platform) or susceptor or pedestal or chuck or platen or (holding adj3 table))	US-PGPUB; USPAT	OR	ON	2007/12/11 07:26
L3	156233	(position\$3 or elevat\$3) adj3 (sensor or detector)	US-PGPUB; USPAT	OR	ON	2007/12/11 07:14
L4	5501	2 and 3	US-PGPUB; USPAT	OR	ON	2007/12/11 07:14
L5	834	4 and (semiconductor adj (process\$3 or product\$3 or manufactur\$3 or treat\$4))	US-PGPUB; USPAT	OR	ON	2007/12/11 07:28
L6	27	5 and laminar	US-PGPUB; USPAT	OR	ON	2007/12/11 07:29
L7	355	(position\$3 or elevat\$3) adj3 ((substrate or wafer or workpiece or work or article) adj3 (holder or table or support or stage or platform) or susceptor or pedestal or chuck or platen or (holding adj3 table)) with ((during or while) adj2 (process\$3 or deposit\$3 or etch\$3))	US-PGPUB; USPAT	OR	ON	2007/12/11 07:27
L8	130	7 and (semiconductor adj (process\$3 or product\$3 or manufactur\$3 or treat\$4))	US-PGPUB; USPAT	OR	ON	2007/12/11 08:08
L9	14	8 and laminar	US-PGPUB; USPAT	OR	ON	2007/12/11 08:08
L10	116	8 not 9	US-PGPUB; USPAT	OR	ON	2007/12/11 07:54
L11	218	((adjust\$3 or mov\$3) adj3 ((substrate or wafer or workpiece or work or article) adj3 (holder or table or support or stage or platform) or susceptor or pedestal or chuck or platen or (holding adj3 table)))) with ((during or while) adj2 (process\$3 or etch\$3 or deposit\$3))	US-PGPUB; USPAT	OR	ON	2007/12/11 08:07
L12	52	11 and (semiconductor adj (process\$3 or product\$3 or manufactur\$3 or treat\$4))	US-PGPUB; USPAT	OR	ON	2007/12/11 09:18
L13	1	12 and laminar	US-PGPUB; USPAT	OR	ON	2007/12/11 08:08

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L17	833	(118/729).CCLS.	US-PGPUB; USPAT	OR	OFF	2007/12/11 09:18
L18	2929	(427/248.1).CCLS.	US-PGPUB; USPAT	OR	OFF	2007/12/11 09:18
L19	3711	17 or 18	US-PGPUB; USPAT	OR	ON	2007/12/11 09:18
S1	1	"10575187"	US-PGPUB; USPAT	OR	ON	2007/12/09 10:24
S2	12	FUTAGAWA near MASAYASU.in. or KAKIMOTO near NORIKO.in.	US-PGPUB; USPAT	OR	ON	2007/12/09 11:19
S3	16537	sharp.as.	US-PGPUB; USPAT	OR	ON	2007/12/09 11:20
S4	10	OKADA near TOSHINORI.in. or TANAKA near "NOBUMASA.in" or ARAKI near YUTAKA.in.	US-PGPUB; USPAT	OR	ON	2007/12/09 11:23
S5	100121	((substrate or wafer or workpiece or work or article) adj3 (holder or table or support or stage or platform) or susceptor or pedestal or chuck or platen or (holding adj3 table)) with (position\$3 or level\$3 or elevat\$3)	US-PGPUB; USPAT	OR	ON	2007/12/09 11:26
S6	1268	S5 and (laminar adj2 flow)	US-PGPUB; USPAT	OR	ON	2007/12/09 11:27
S7	613	S6 and ((vapor adj deposition) or CVD)	US-PGPUB; USPAT	OR	ON	2007/12/09 11:34
S8	39	S7 and (store\$1 adj2 (information or data))	US-PGPUB; USPAT	OR	ON	2007/12/09 11:35
S9	41514	((substrate or wafer or workpiece or work or article) adj3 (holder or table or support or stage or platform) or susceptor or pedestal or chuck or platen or (holding adj3 table)) with (before or after)	US-PGPUB; USPAT	OR	ON	2007/12/10 17:14
S10	4314	position\$3 with (before or after) with (pressure or heat\$3 or flow) with (start\$3 or beginning)	US-PGPUB; USPAT	OR	ON	2007/12/10 17:27
S11	13	(position\$3 adj3 ((substrate or wafer or workpiece or work or article) adj3 (holder or table or support or stage or platform) or susceptor or pedestal or chuck or platen or (holding adj3 table))) with (before or after) with (pressure or heat\$3 or flow) with (start\$3 or beginning)	US-PGPUB; USPAT	OR	ON	2007/12/10 18:00

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S12	78	S10 and (semiconductor adj (process\$3 or product\$3 or manufactur\$3 or treat\$4))	US-PGPUB; USPAT	OR	ON	2007/12/11 07:14
S14	30280	(((substrate or wafer or workpiece or work or article) adj3 (holder or table or support or stage or platform) or susceptor or pedestal or chuck or platen or (holding adj3 table))) near3 (start\$3 or beginning or first)	US-PGPUB; USPAT	OR	ON	2007/12/10 18:01
S15	19329	(((position\$3 or elevat\$3 or set\$4) adj3 (substrate or wafer or workpiece or work or article) adj3 (holder or table or support or stage or platform) or susceptor or pedestal or chuck or platen or (holding adj3 table))) near3 (start\$3 or beginning or first)	US-PGPUB; USPAT	OR	ON	2007/12/10 18:38
S16	1656	S15 and (semiconductor adj (process\$3 or product\$3 or manufactur\$3 or treat\$4))	US-PGPUB; USPAT	OR	ON	2007/12/10 18:40
S17	81	S16 and laminar	US-PGPUB; USPAT	OR	ON	2007/12/10 18:40
S18	24014	(((position\$3 or elevat\$3 or set\$4) adj3 (substrate or wafer or workpiece or work or article) adj3 (holder or table or support or stage or platform) or susceptor or pedestal or chuck or platen or (holding adj3 table))) near3 (last or end or subsequent or next)	US-PGPUB; USPAT	OR	ON	2007/12/10 18:53
S19	1477	S18 with (temperature or thermal or pressure)	US-PGPUB; USPAT	OR	ON	2007/12/10 18:39
S20	73	S19 and (semiconductor adj (process\$3 or product\$3 or manufactur\$3 or treat\$4))	US-PGPUB; USPAT	OR	ON	2007/12/10 18:56
S21	13	S20 and laminar	US-PGPUB; USPAT	OR	ON	2007/12/10 18:56
S22	5946	((after adj3 (position\$3 or elevat\$3 or set\$4) adj3 (substrate or wafer or workpiece or work or article) adj3 (holder or table or support or stage or platform) or susceptor or pedestal or chuck or platen or (holding adj3 table))) same (temperature with pressure)	US-PGPUB; USPAT	OR	ON	2007/12/10 18:55

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S23	5944	((before adj3 (position\$3 or elevat\$3 or set\$4) adj3 (substrate or wafer or workpiece or work or article) adj3 (holder or table or support or stage or platform) or susceptor or pedestal or chuck or platen or (holding adj3 table))) same (temperature with pressure)	US-PGPUB; USPAT	OR	ON	2007/12/11 07:12
S24	1099	S23 and (semiconductor adj (process\$3 or product\$3 or manufactur\$3 or treat\$4))	US-PGPUB; USPAT	OR	ON	2007/12/10 19:01
S25	102	S24 and laminar	US-PGPUB; USPAT	OR	ON	2007/12/11 07:15
S27	84	((before with ((position\$3 or elevat\$3 or set\$4) adj3 (substrate or wafer or workpiece or work or article) adj3 (holder or table or support or stage or platform) or susceptor or pedestal or chuck or platen or (holding adj3 table)))) same (temperature with pressure)	US-PGPUB; USPAT	OR	ON	2007/12/10 19:01
S28	13	S27 and (semiconductor adj (process\$3 or product\$3 or manufactur\$3 or treat\$4))	US-PGPUB; USPAT	OR	ON	2007/12/10 19:12
S29	1	S28 and laminar	US-PGPUB; USPAT	OR	ON	2007/12/10 19:12
S34	43	((adjust\$3 adj3 (position\$3 or elevat\$3 or height or level) adj3 ((substrate or wafer or workpiece or work or article) adj3 (holder or table or support or stage or platform) or susceptor or pedestal or chuck or platen or (holding adj3 table)))) with during	US-PGPUB; USPAT	OR	ON	2007/12/11 08:05
S36	6	S34 and (semiconductor adj (process\$3 or product\$3 or manufactur\$3 or treat\$4))	US-PGPUB; USPAT	OR	ON	2007/12/10 19:17